

# A Direct Comparison of Inverted and Non-inverted Growths of GaInP Solar Cells

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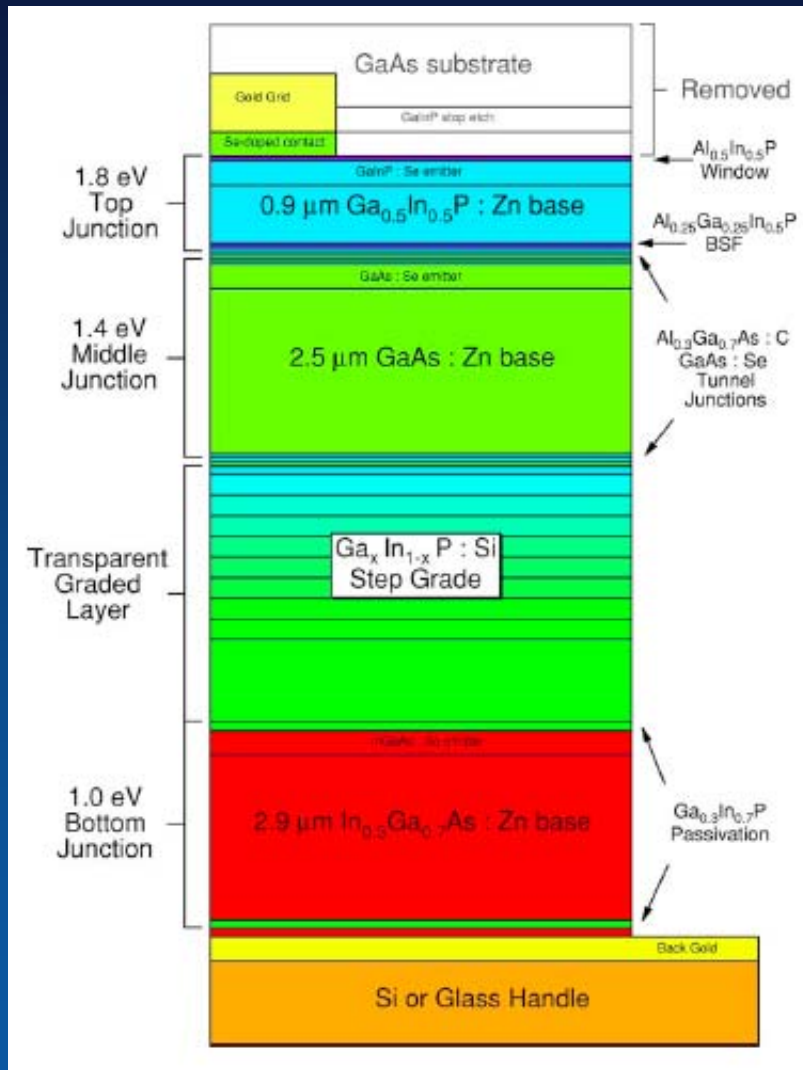
# Motivation

Growing inverted cells may enable technological advances in solar cell fabrication, leading to higher efficiencies.

Differences in dopant diffusion during inverted vs. upright growths may lead to:

- Differences in atomic depth profiles
- Changes in carrier concentrations
- Higher contact resistance
- Lower overall performance

# Inverted triple junction



Geisz *et al.*, APL **91**, 023502 (2007)

Geisz *et al.*, 33<sup>rd</sup> PVSC (2008)

1.0-eV lattice-mismatched InGaAs bottom subcell enables a higher total efficiency: 39.2% @131 suns.

Growing the bottom subcell last avoids threading the middle and top subcells with dislocations.

# This talk...

Solar cell characteristics

SIMS depth profiles analysis

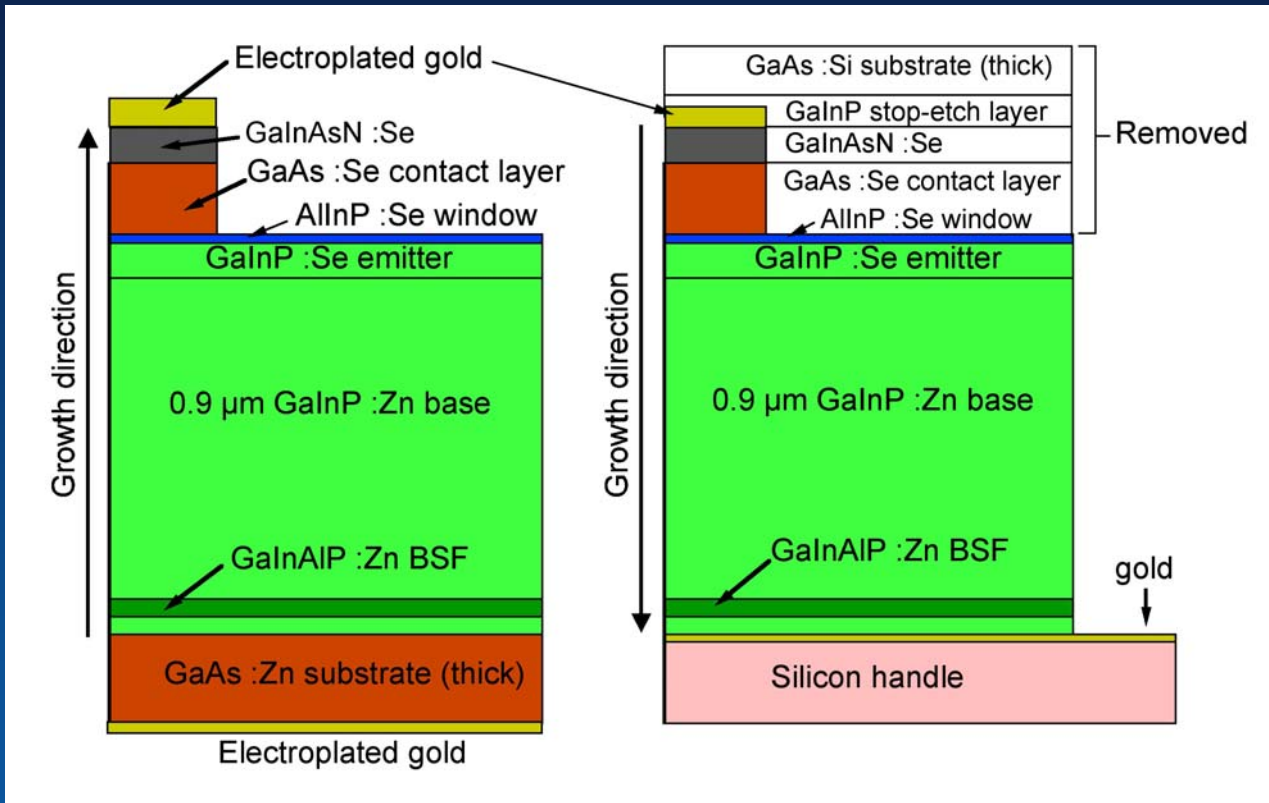
Top contact resistance

Selenium diffusion in GaInAsN

# Layer structures

## Upright growth

## Inverted growth

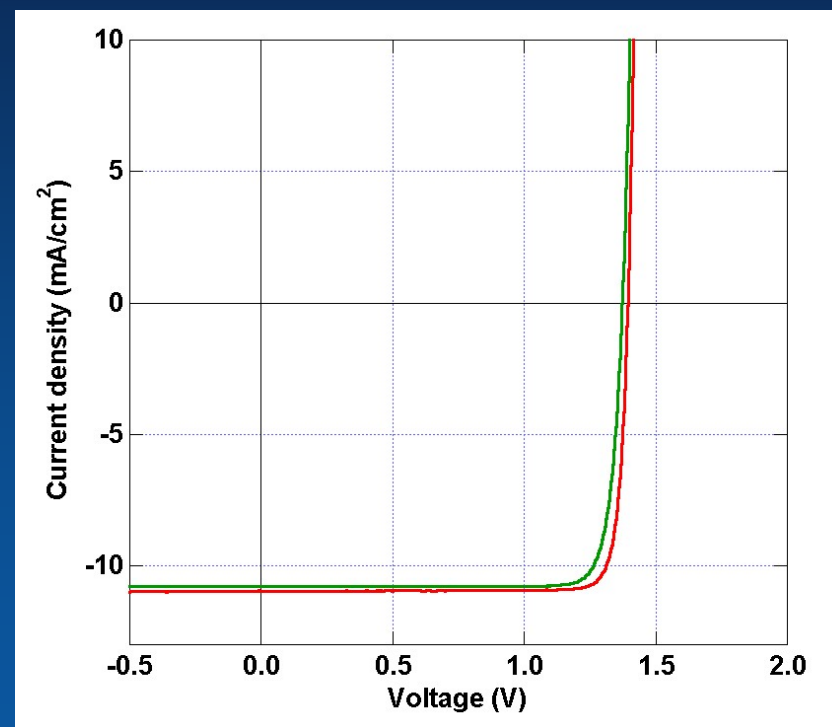
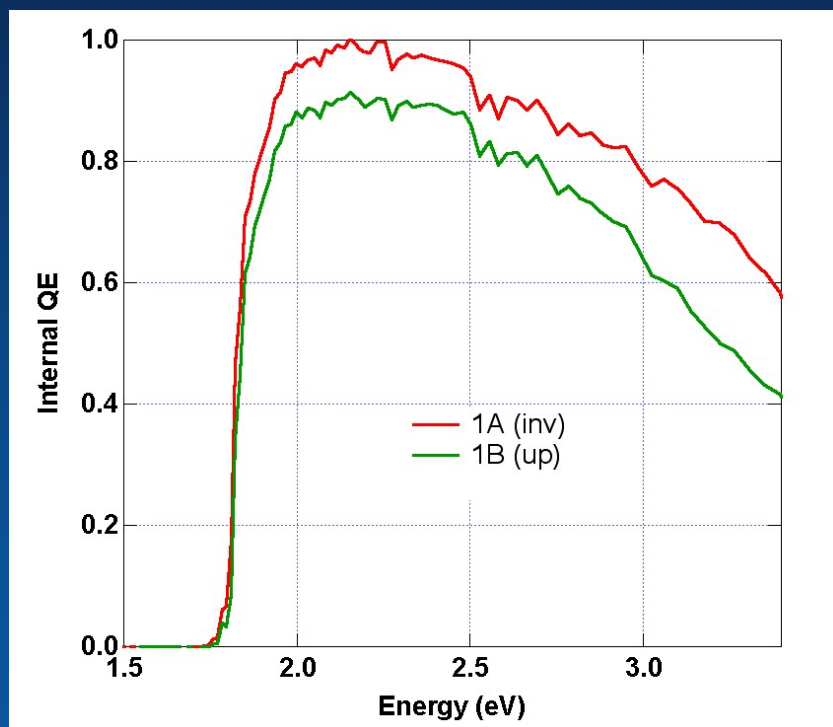


OMPVE  
 Atmospheric pressure  
 Vertical reactor

Precursors:  
 Trimethylgallium  
 Triethylgallium  
 Trimethylindium  
 Trimethylaluminum  
 Arsine  
 Phosphine  
 Dimethylhydrazine  
 Diethylzinc  
 Hydrogen selenide

# Solar cell characteristics (optimized for inverted growth)

		$R_s$ ( $\Omega/\text{sqr}$ )	$R_c$ ( $\text{m}\Omega\text{-cm}^2$ )	Emitter ( $10^{18} \text{ cm}^{-3}$ )	Base ( $10^{16} \text{ cm}^{-3}$ )	Voc (V)	Jsc ( $\text{mA}/\text{cm}^2$ )	FF (%)	Eff (%)
1A	inv	326	0.088	-3.2	1.4	1.395	10.97	88.3	13.5
1B	up	981	0.11	-0.98	0.34	1.372	10.79	86.8	12.9



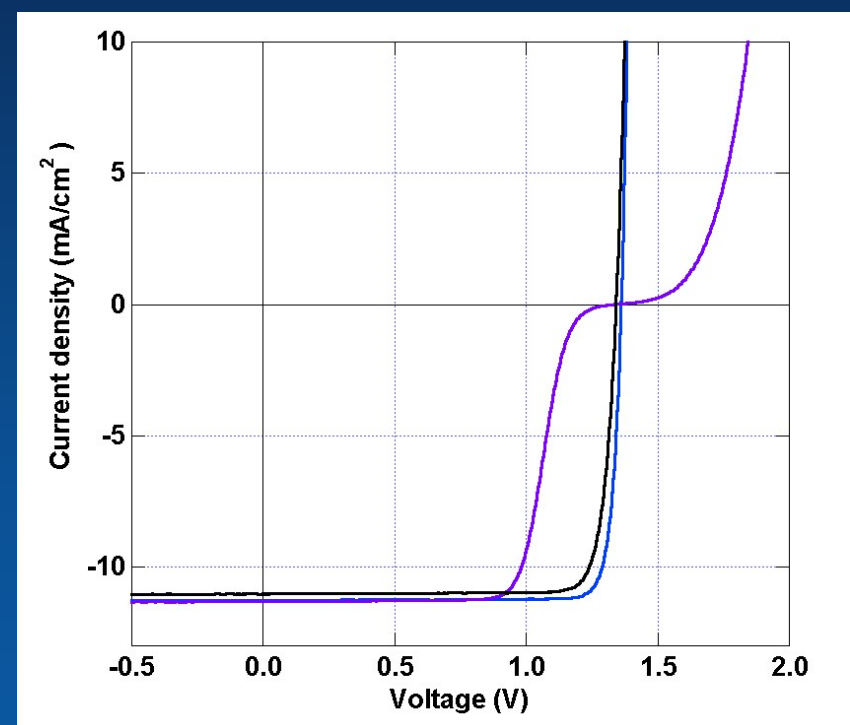
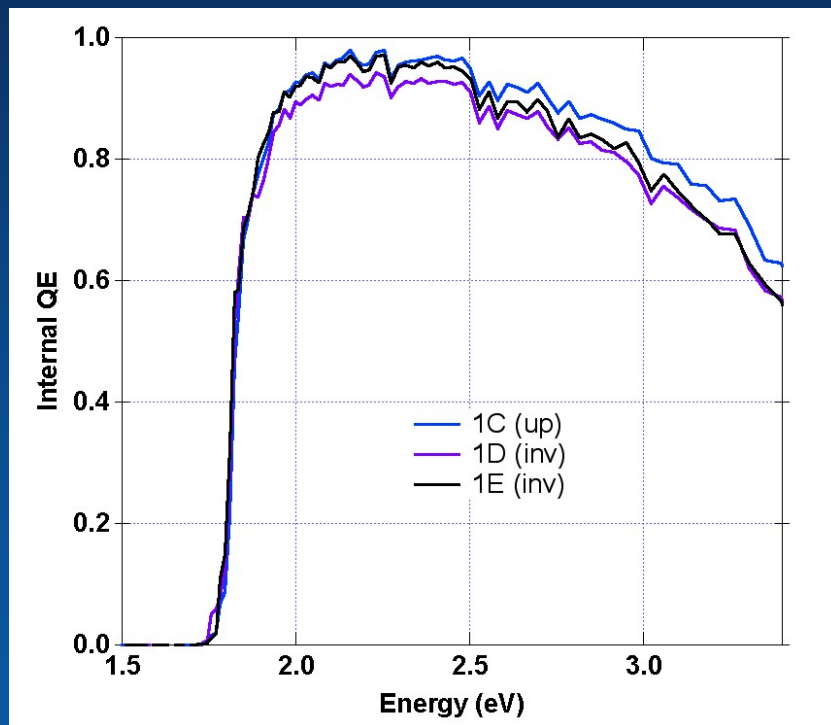
GalnAsN contacts for 1A and 1B

XT-10

GalnP reference cell calibrated for lowAOD

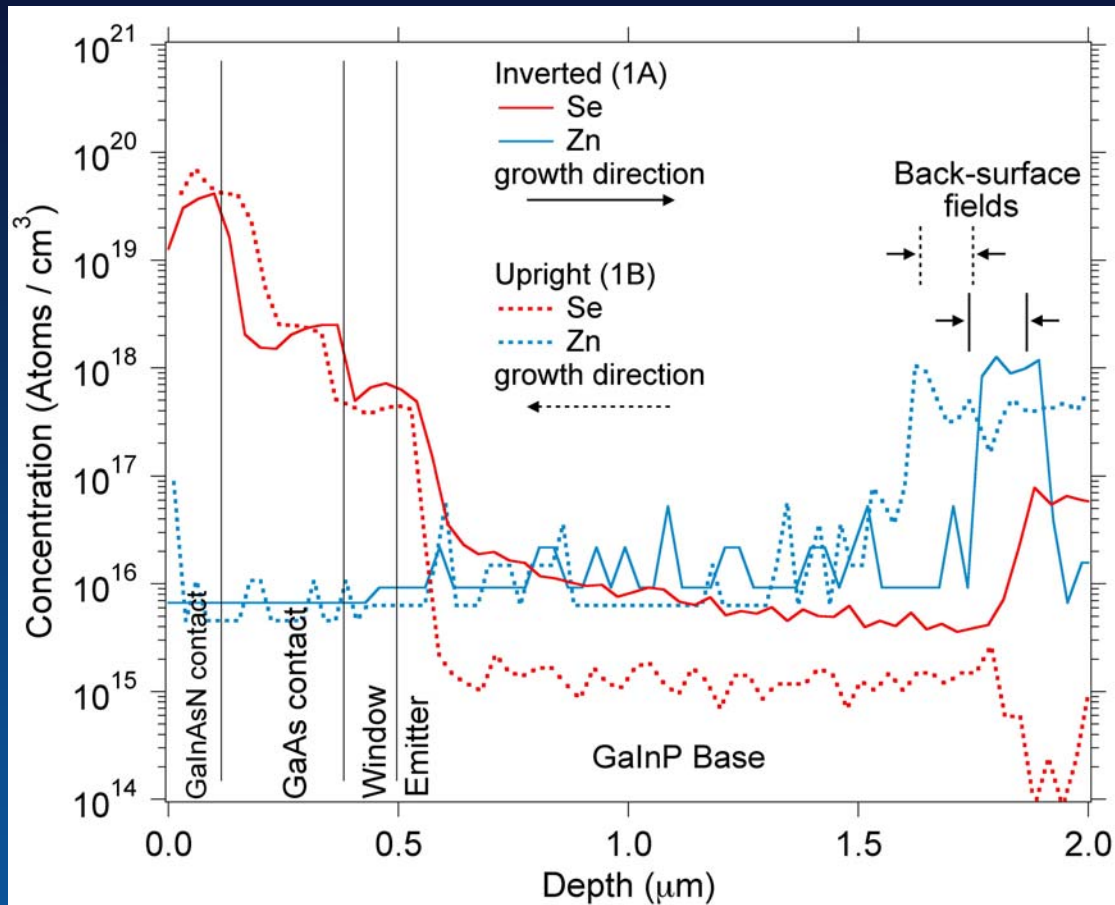
# Solar cell characteristics (optimized for upright growth)

		$R_s$ ( $\Omega/\text{sqr}$ )	$R_c$ ( $m\Omega\text{-cm}^2$ )	Emitter ( $10^{18} \text{ cm}^{-3}$ )	Base ( $10^{16} \text{ cm}^{-3}$ )	$V_{oc}$ (V)	$J_{sc}$ ( $\text{mA}/\text{cm}^2$ )	FF (%)	Eff (%)
1C	up	600	0.50	-1.7	9.1	1.361	11.27	88.6	13.6
1D	inv	--	--	--	4.5	1.306	11.31	68.7	10.2
1E	inv	516	0.22	-2.1	3.1	1.340	11.03	86.3	12.8



GaAs contacts for 1C and 1D; GaInAsN contacts for 1E

# SIMS on inverted-upright pair (1A-1B)



Junction depth

Selenium tails

Zinc tails at BSF

Window layer doping

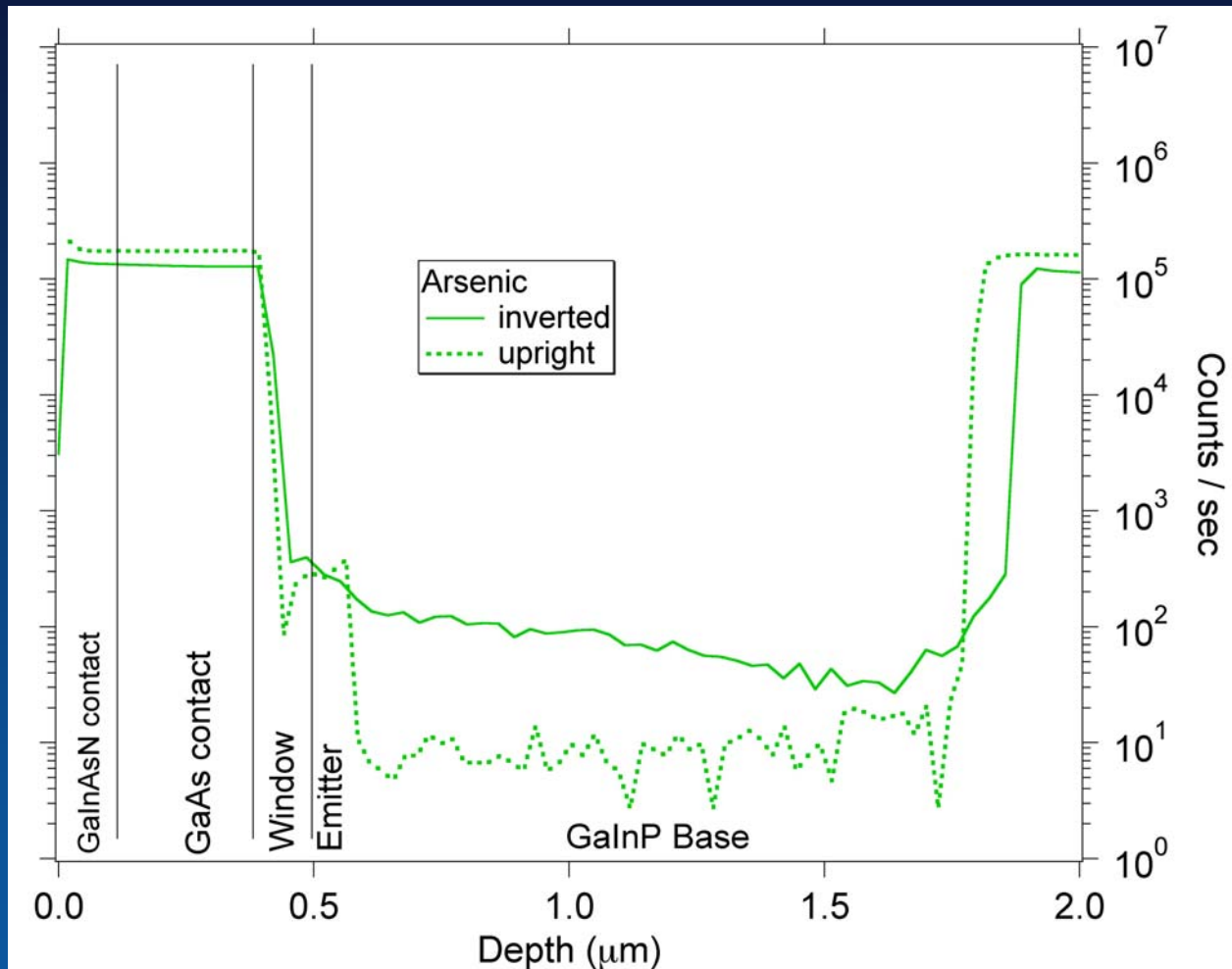
Contact layer doping

Cell thickness

		$R_s$ ( $\Omega/\text{sqr}$ )	$R_c$ ( $\text{m}\Omega\text{-cm}^2$ )	Emitter ( $10^{18} \text{ cm}^{-3}$ )	Base ( $10^{16} \text{ cm}^{-3}$ )	$V_{oc}$ (V)	$J_{sc}$ ( $\text{mA}/\text{cm}^2$ )	FF (%)	Eff (%)
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# SIMS, cont'd (arsenic)

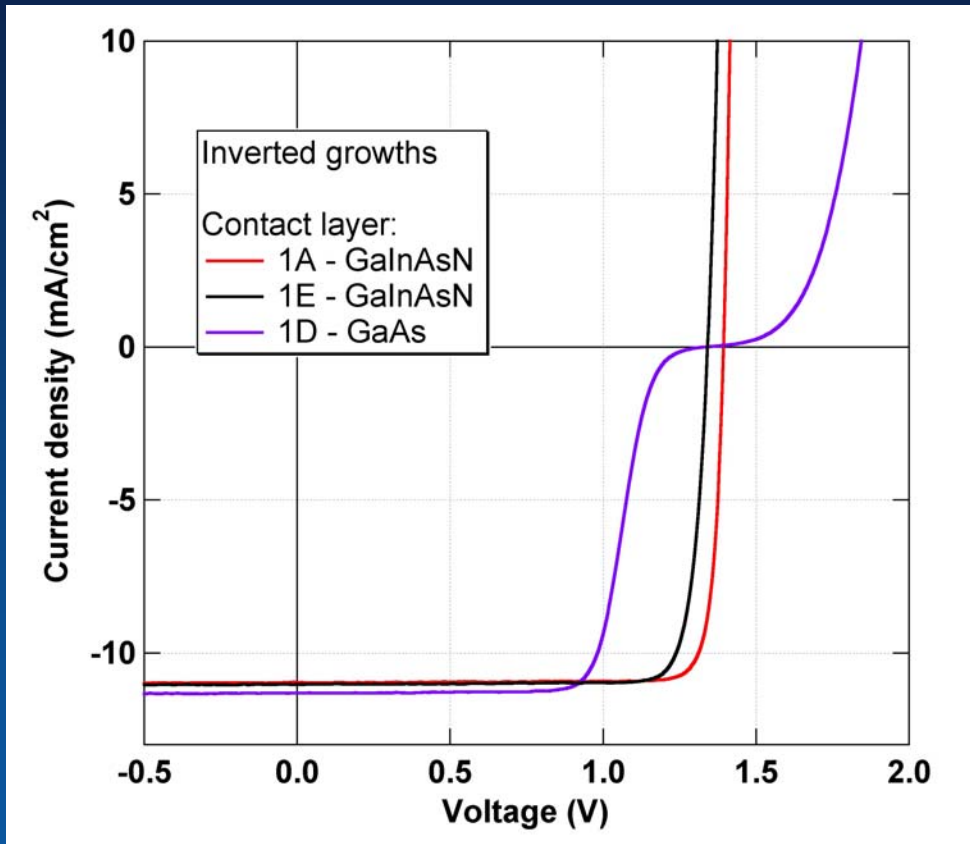


Long arsenic tail in the inverted cell

→ memory effect in the growth reactor.

# Effect of the top contact layer

JV curves for all inverted growths



Introducing N has been found to:

(1) lower the bandgap  
(GaInAsN with ~1% N  
has  $E_g \sim 1.1$  eV)

→ Lower contact resistance

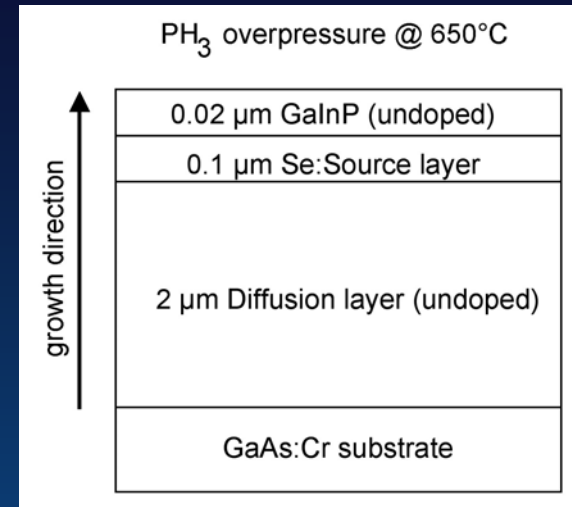
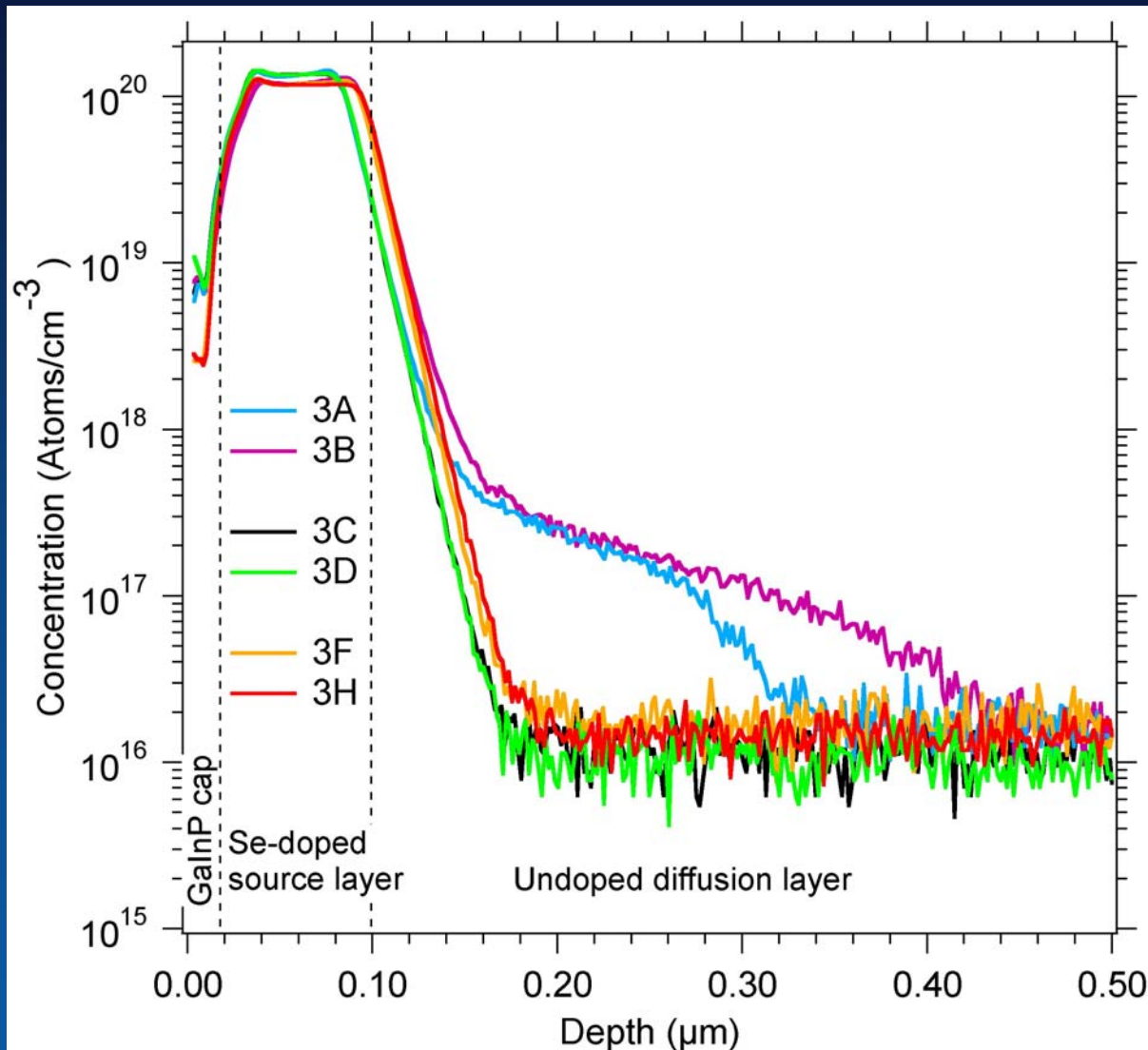
(2) increase the effective mass

→ Higher carrier concentration

We speculate that it will also:

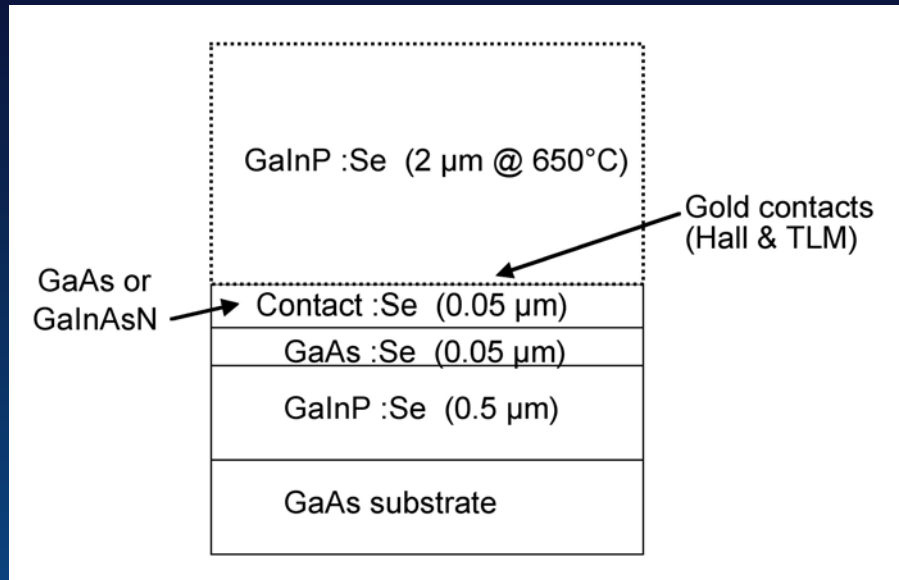
(3) inhibit diffusion

# Diffusion in GaInAsN



3A	Se:GaAs / GaAs (not annealed)
3B	Se:GaAs / GaAs
3C	Se:GaAs / GaInAsN (not annealed)
3D	Se:GaAs / GaInAsN
3F	Se:GaInAsN / GaInAsN
3H	Se:GaInAsN / GaAs

# Contact resistance study



GaInAsN composition:  
~1% N  
2% In for lattice-matching to GaAs

Contact layer grown at 570°C

Sample	Contact layer	Specific contact resistance ( $\text{m}\Omega\text{-cm}^2$ )
2A	GaAs (not annealed)	0.013
2B	GaAs (annealed)	1.98
2C	GaInAsN (not annealed)	0.003
2D	GaInAsN (annealed)	0.020

# Summary

Excellent performance is achievable in both upright and inverted configurations with proper consideration.

Subtle differences in depth profile, QE and JV between upright and inverted growths due to dopant diffusion.

GaNAsN contact layer is resilient to lengthy annealing; more work necessary to determine why.

# Acknowledgements

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